



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Thakar et al

Serial No. 10/645,032

Filed: 08/21/2003

For: POLYSILICON PROCESSING USING AN ANTI-REFLECTIVE  
DUAL LAYER HARDMASK FOR 193 nm LITHOGRAPHY

Customer Service Center

Initial Examination Division

Docket: TI-32822.1

Commissioner for Patents

PO Box 1450

Alexandria, Virginia 22313-1450

Sir:

PRELIMINARY AMENDMENT

On page 1 of the Specification, before the first paragraph, please insert the following:

-- This application is a Division of 09/939,259 filed 08/24/2001, now U.S. 6,624,068. --

Respectfully submitted,

Gary C. Honeycutt, Reg.No. 20,250

Attorney for Applicant

972-470-0130

1-17-04